

SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,
RESIST COMPOSITION EMPLOYING IT, PATTERN-FORMING METHOD
AND ELECTRONIC DEVICE FABRICATION METHOD

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ABSTRACT OF THE DISCLOSURE

10 A silicon-containing polymer having a tetrafunctional siloxane portion as the basic skeleton, and containing a carboxylic acid group-containing triorganosiloxane portion and a carboxylic acid derivative group-containing triorganosiloxane portion in a specific proportion. It may be advantageously used as a negative non-chemical amplification resist polymer or a positive chemical amplification resist polymer.